

=> d his

(FILE 'HOME' ENTERED AT 17:54:47 ON 29 SEP 2004)

FILE 'REGISTRY' ENTERED AT 17:55:10 ON 29 SEP 2004

L1 SCREEN 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 1 S L3 SSS SAM
L5 SCREEN 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 0 S L7 SSS SAM
L9 SCREEN 2067
L10 STRUCTURE UPLOADED
L11 QUE L10 AND L9
L12 5 S L11 SSS SAM
L13 SCREEN 2067
L14 STRUCTURE UPLOADED
L15 QUE L14 AND L13
L16 16 S L15 SSS SAM
L17 SCREEN 2067
L18 STRUCTURE UPLOADED
L19 QUE L18 AND L17
L20 50 S L19 SSS SAM
L21 6 S L4 OR L8 OR L12
L22 0 S L21 AND L16 AND L20

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 17:57:38 ON 29 SEP 2004

L23 0 S L22
L24 125 S L20
L25 0 S L22
L26 15 S L21
L27 0 S L24 AND L26
L28 7 DUPLICATE REMOVE L26 (8 DUPLICATES REMOVED)

=> duplicates remove l24

DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L24

L29 62 DUPLICATE REMOVE L24 (63 DUPLICATES REMOVED)

=> s l29 and l20

L30 62 L29 AND L20

=> s l16 and l20

L31 0 L16 AND L20

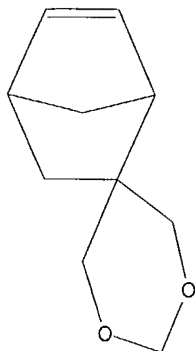
=> s l16 and l21

L32 0 L16 AND L21

=> s l20 and l21

L33 0 L20 AND L21

=> d
L3 HAS NO ANSWERS
L1 SCR 2067
L2 STR



G1 O,N

Structure attributes must be viewed using STN Express query preparation.
L3 QUE ABB=ON PLU=ON L2 AND L1

=> s l3 sss sam
SAMPLE SEARCH INITIATED 17:55:28 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 5 TO ITERATE

100.0% PROCESSED 5 ITERATIONS 1 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 5 TO 234
PROJECTED ANSWERS: 1 TO 80

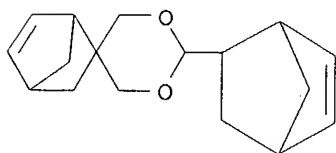
L4 1 SEA SSS SAM L2 AND L1

=> d

L4 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2004 ACS on STN
RN 32731-90-1 REGISTRY
CN Acrylic acid, polymer with endo-2-(5-norbornen-2-yl)spiro[m-dioxane-5,2'-
[5]norbornene] (8CI) (CA INDEX NAME)
MF (C17 H22 O2 . C3 H4 O2)x
CI PMS
PCT Polyacrylic, Polyether
LC STN Files: CA, CAPLUS
DT.CA CAplus document type: Patent
RL.P Roles from patents: PREP (Preparation)

CM 1

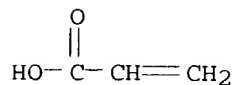
CRN 3781-34-8
CMF C17 H22 O2



CM 2

CRN 79-10-7

CMF C3 H4 O2



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L5 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10150083-2.str

L6 STRUCTURE UPLOADED

=> que L6 AND L5

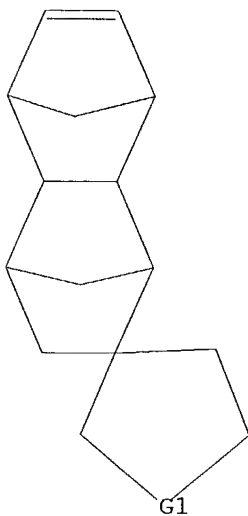
L7 QUE L6 AND L5

=> d

L7 HAS NO ANSWERS

L5 SCR 2067

L6 STR



G1 O,N

Structure attributes must be viewed using STN Express query preparation.
L7 QUE ABB=ON PLU=ON L6 AND L5

=> s 17 sss sam
SAMPLE SEARCH INITIATED 17:55:59 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 19 TO ITERATE

100.0% PROCESSED 19 ITERATIONS 0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 119 TO 641
PROJECTED ANSWERS: 0 TO 0

L8 0 SEA SSS SAM L6 AND L5

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L9 SCREEN CREATED

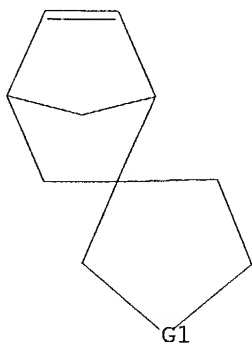
=>
Uploading C:\Program Files\Stnexp\Queries\10150083-1.str

L10 STRUCTURE UPLOADED

=> que L10 AND L9

L11 QUE L10 AND L9

=> d
L11 HAS NO ANSWERS
L9 SCR 2067
L10 STR



G1 O,N

Structure attributes must be viewed using STN Express query preparation.
L11 QUE ABB=ON PLU=ON L10 AND L9

=> s 111 sss sam
SAMPLE SEARCH INITIATED 17:56:20 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 32 TO ITERATE

100.0% PROCESSED 32 ITERATIONS
SEARCH TIME: 00.00.01

5 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 301 TO 979
PROJECTED ANSWERS: 5 TO 234

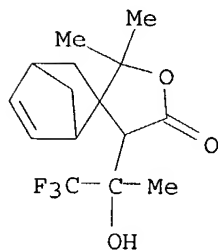
L12 5 SEA SSS SAM L10 AND L9

=> d

L12 ANSWER 1 OF 5 REGISTRY COPYRIGHT 2004 ACS on STN
RN 701294-45-3 REGISTRY
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer
with 2',2'-dimethyl-4'-(2,2,2-trifluoro-1-hydroxy-1-
methylethyl)spiro[bicyclo[2.2.1]hept-5-ene-2,3' (2'H)-furan]-5' (4'H)-one
(9CI) (CA INDEX NAME)
MF (C15 H19 F3 O3 . C8 H11 F3 O2)x
CI PMS
PCT Polyacrylic, Polyester, Polyester formed, Polyvinyl
SR CA
LC STN Files: CA, CAPLUS
DT.CA Caplus document type: Patent
RL.P Roles from patents: PREP (Preparation); USES (Uses)

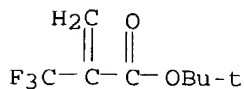
CM 1

CRN 701294-44-2
CMF C15 H19 F3 O3



CM 2

CRN 105935-24-8
CMF C8 H11 F3 O2



1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L13 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10150083-4.str

L14 STRUCTURE UPLOADED

=> que L14 AND L13

L15 QUE L14 AND L13

=> d

L15 HAS NO ANSWERS

L13 SCR 2067

L14 STR

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

Structure attributes must be viewed using STN Express query preparation.

L15 QUE ABB=ON PLU=ON L14 AND L13

=> s l15 sss sam

SAMPLE SEARCH INITIATED 17:56:55 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 31 TO ITERATE

100.0% PROCESSED 31 ITERATIONS

16 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 286 TO 954

PROJECTED ANSWERS: 80 TO 560

L16 16 SEA SSS SAM L14 AND L13

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L17 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\maleicanhydride.str

L18 STRUCTURE UPLOADED

=> que L18 AND L17

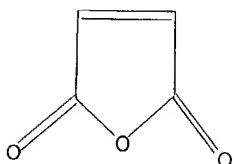
L19 QUE L18 AND L17

=> d

L19 HAS NO ANSWERS

L17 SCR 2067

L18 STR



Structure attributes must be viewed using STN Express query preparation.
 L19 QUE ABB=ON PLU=ON L18 AND L17

=> s l19 sss sam
 SAMPLE SEARCH INITIATED 17:57:17 FILE 'REGISTRY'
 SAMPLE SCREEN SEARCH COMPLETED - 3728 TO ITERATE

26.8% PROCESSED 1000 ITERATIONS 50 ANSWERS
 INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
 SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
 BATCH **COMPLETE**
 PROJECTED ITERATIONS: 70899 TO 78221
 PROJECTED ANSWERS: 58693 TO 65373

L20 50 SEA SSS SAM L18 AND L17

=> s l4 or l8 or l12
 L21 6 L4 OR L8 OR L12

=> s l21 and l16 and l20
 L22 0 L21 AND L16 AND L20

=> FIL HCAPLUS, CAPLUS, USPATFULL		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	5.22	5.43

FILE 'HCAPLUS' ENTERED AT 17:57:38 ON 29 SEP 2004
 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
 PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
 COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 17:57:38 ON 29 SEP 2004
 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
 PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
 COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 17:57:38 ON 29 SEP 2004
 CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l22
 L23 0 L22

=> s l20
 L24 125 L20

=> s l22
 L25 0 L22

=> s l21
 L26 15 L21

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1096318	A1	20010502	EP 2000-309392	20001025
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
	JP 2001125270	A2	20010511	JP 1999-302909	19991025
	TW 554245	B	20030921	TW 2000-89122347	20001024
	US 6667145	B1	20031223	US 2000-694369	20001024
PRAI	JP 1999-302909	A	19991025		
RE.CNT	3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT				

L28 ANSWER 7 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 6
AN 1971:437044 HCAPLUS
DN 75:37044
TI Polymerization of monoolefins containing carboxylic acid groups with cyclic dienes
IN Ihlein, Walter; Galinke, Joachim
PA Henkel und Cie. G.m.b.H.
SO Ger. Offen., 11 pp.
CODEN: GWXXBX
DT Patent
LA German

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 1948198	A	19710401	DE 1969-1948198	19690924
	DE 1948198	B2	19800703		
	DE 1948198	C3	19810312		
PRAI	DE 1969-1948198		19690924		

=> d l28 1-7 ibib hitstr

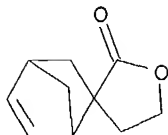
L28 ANSWER 1 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2004:33988 HCAPLUS
DOCUMENT NUMBER: 140:94885
TITLE: Preparation of copolymers from unsaturated alicyclic monomers
INVENTOR(S): Brock, Phillip J.; Kobayashi, Eiichi; Nishimura, Isao; Nishimura, Yukio; Wallow, Thomas I.; Yamamoto, Masafumi
PATENT ASSIGNEE(S): International Business Machines Corporation, USA; JSR Corporation
SOURCE: U.S., 25 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	US 6677419	B1	20040113	US 2002-293740	20021113
PRIORITY APPLN. INFO.:				US 2002-293740	20021113
IT	644966-25-6P				
	RL: IMF (Industrial manufacture); PRP (Properties); PREP (Preparation) (preparation of copolymers from unsatd. alicyclic monomers)				
RN	644966-25-6 HCAPLUS				
CN	2-Propenoic acid, (1R,2R,4R)-1,7,7-trimethylbicyclo[2.2.1]hept-2-yl ester, rel-, polymer with 4',5'-dihydrospiro[bicyclo[2.2.1]hept-5-ene-2,3'(2'H)-furan]-2'-one (9CI) (CA INDEX NAME)				

CM 1

CRN 72377-80-1

CMF C10 H12 O2

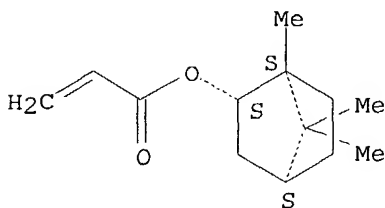


CM 2

CRN 5888-33-5

CMF C13 H20 O2

Relative stereochemistry.



REFERENCE COUNT: 33 THERE ARE 33 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L28 ANSWER 2 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2

ACCESSION NUMBER: 2004:472366 HCAPLUS

DOCUMENT NUMBER: 141:44850

TITLE: Unsaturated monomers bearing fluorine-containing bridged alicyclic lactone structures, their polymers, and chemically amplified resists and pattern formation using them

INVENTOR(S): Maeda, Katsumi; Nakano, Kaichiro

PATENT ASSIGNEE(S): NEC Corp., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 36 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004161827	A2	20040610	JP 2002-327075	20021111
PRIORITY APPLN. INFO.:			JP 2002-327075	20021111
OTHER SOURCE(S):	MARPAT	141:44850		

IT 701294-45-3P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(chemical amplified photoresists for F2 excimer laser exposure containing polymers from F-containing bridged alicyclic lactone monomers)

RN 701294-45-3 HCAPLUS

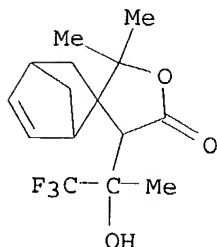
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 2',2'-dimethyl-4'-(2,2,2-trifluoro-1-hydroxy-1-

methylethyl)spiro[bicyclo[2.2.1]hept-5-ene-2,3' (2'H)-furan]-5' (4'H)-one
(9CI) (CA INDEX NAME)

CM 1

CRN 701294-44-2

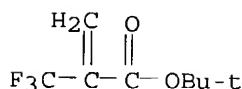
CMF C15 H19 F3 O3



CM 2

CRN 105935-24-8

CMF C8 H11 F3 O2



L28 ANSWER 3 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 3

ACCESSION NUMBER: 2003:355687 HCAPLUS

DOCUMENT NUMBER: 138:376401

TITLE: Polymer and resist composition for deep-UV and electron beam patterning process

INVENTOR(S): Nishi, Tsunehiro; Hasegawa, Koji; Kinsho, Takeshi

PATENT ASSIGNEE(S): Japan

SOURCE: U.S. Pat. Appl. Publ., 29 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003087183	A1	20030508	US 2002-230341	20020829
JP 2003147023	A2	20030521	JP 2002-244664	20020826
TW 578035	B	20040301	TW 2002-91119897	20020830
			JP 2001-262833	A 20010831

PRIORITY APPLN. INFO.:

IT 521950-67-4P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(polymer and resist composition for deep-UV and electron beam patterning process)

RN 521950-67-4 HCAPLUS

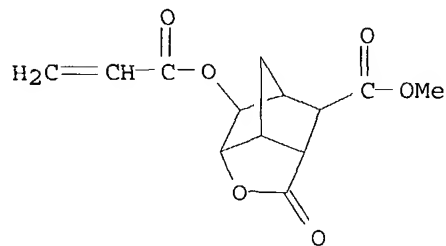
CN 3,5-Methano-2H-cyclopenta[b]furan-7-carboxylic acid, hexahydro-2-oxo-6-[(1-oxo-2-propenyl)oxy]-, methyl ester, polymer with 2,5-furandione, 2-methyltricyclo[3.3.1.1^{3,7}]dec-2-yl 2-propenoate and spiro[bicyclo[2.2.1]hept-5-ene-2,3' (2'H)-furan]-5' (4'H)-one (9CI) (CA

INDEX NAME)

CM 1

CRN 449759-66-4

CMF C13 H14 O6



CM 2

CRN 282542-79-4

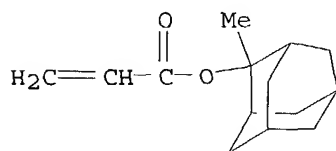
CMF C10 H12 O2



CM 3

CRN 249562-06-9

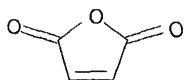
CMF C14 H20 O2



CM 4

CRN 108-31-6

CMF C4 H2 O3



L28 ANSWER 4 OF 7 USPATFULL on STN

ACCESSION NUMBER: 2003:332321 USPATFULL

TITLE: Resist composition and patterning process

INVENTOR(S): Nishi, Tsunehiro, Nakakubiki-gun, JAPAN

Watanabe, Takeru, Nakakubiki-gun, JAPAN
 Kinsho, Takeshi, Nakakubiki-gun, JAPAN
 Hasegawa, Koji, Nakakubiki-gun, JAPAN
 Kobayashi, Tomohiro, Nakakubiki-gun, JAPAN
 Hatakeyama, Jun, Nakakubiki-gun, JAPAN
 Shin-Etsu Chemical Co., Ltd., Tokyo, JAPAN (non-U.S.
 corporation)

PATENT ASSIGNEE(S):

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6667145	B1	20031223
APPLICATION INFO.:	US 2000-694369		20001024 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-302909	19991025
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	GRANTED	
PRIMARY EXAMINER:	Baxter, Janet	
ASSISTANT EXAMINER:	Lee, Sin J.	
LEGAL REPRESENTATIVE:	Millen, White, Zelano, Branigan, P.C.	
NUMBER OF CLAIMS:	17	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	0 Drawing Figure(s); 0 Drawing Page(s)	
LINE COUNT:	1465	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.		
IT 336620-32-7P		

(resist composition containing cyclic polymer base resin having highly adherent

and rigid units suitable as micropatterning material for VLSI fabrication)

RN 336620-32-7 USPATFULL

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1-ethyl-2-cyclohexen-1-yl ester, polymer with spiro[bicyclo[2.2.1]hept-5-ene-2,3'(2'H)-furan]-5'(4'H)-one (9CI) (CA INDEX NAME)

CM 1

CRN 282542-79-4

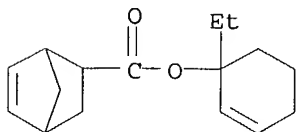
CMF C10 H12 O2



CM 2

CRN 279243-73-1

CMF C16 H22 O2



L28 ANSWER 5 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 4

ACCESSION NUMBER: 2002:830059 HCAPLUS

DOCUMENT NUMBER: 137:338757

TITLE: Imide-containing cyclic olefin (co)polymers for optical materials, films or sheets, adhesives, coatings, and composites with silica and/or alumina

INVENTOR(S): Kaizu, Michitaka; Oshima, Noboru

PATENT ASSIGNEE(S): JSR Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

10-31-02

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002317014	A2	20021031	JP 2001-39941	20010216
PRIORITY APPLN. INFO.:			JP 2001-38711	A 20010215

IT 473916-00-6P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(imide-containing cycloolefin polymers for optical materials, films or sheets, adhesives, coatings, and composites with silica and/or alumina)

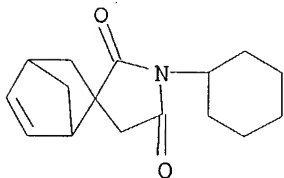
RN 473916-00-6 HCAPLUS

CN Spiro[bicyclo[2.2.1]hept-5-ene-2,3'-pyrrolidine]-2',5'-dione, 1'-cyclohexyl-, polymer with bicyclo[2.2.1]hept-2-ene and 5-hexylbicyclo[2.2.1]hept-2-ene (9CI) (CA INDEX NAME)

CM 1

CRN 110513-35-4

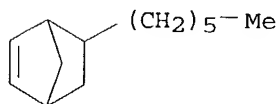
CMF C16 H21 N O2



CM 2

CRN 22094-83-3

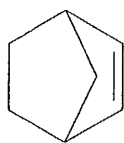
CMF C13 H22



CM 3

CRN 498-66-8

CMF C7 H10



L28 ANSWER 6 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 5
 ACCESSION NUMBER: 2001:319604 HCAPLUS
 DOCUMENT NUMBER: 134:334290
 TITLE: Resist composition and patterning process
 INVENTOR(S): Nishi, Tsunehiro; Watanabe, Takeru; Kinsho, Takeshi;
 Hasegawa, Koji; Kobayashi, Tomohiro; Hatakeyama, Jun
 PATENT ASSIGNEE(S): Shin-Etsu Chemical Co., Ltd., Japan
 SOURCE: Eur. Pat. Appl., 45 pp.
 CODEN: EPXXDW
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

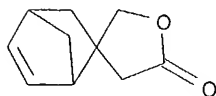
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1096318	A1	20010502	EP 2000-309392	20001025
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO				
JP 2001125270	A2	20010511	JP 1999-302909	19991025
TW 554245	B	20030921	TW 2000-89122347	20001024
US 6667145	B1	20031223	US 2000-694369	20001024
PRIORITY APPLN. INFO.:			JP 1999-302909	A 19991025

IT **336620-32-7P**
 RL: DEV (Device component use); PEP (Physical, engineering or chemical process); POF (Polymer in formulation); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
 (resist composition containing cyclic polymer base resin having highly adherent and rigid units suitable as micropatterning material for VLSI fabrication)

RN 336620-32-7 HCAPLUS
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1-ethyl-2-cyclohexen-1-yl ester, polymer with spiro[bicyclo[2.2.1]hept-5-ene-2,3'(2'H)-furan]-5'(4'H)-one (9CI) (CA INDEX NAME)

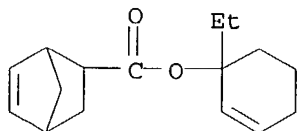
CM 1

CRN 282542-79-4
 CMF C10 H12 O2



CM 2

CRN 279243-73-1
 CMF C16 H22 O2



REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L28 ANSWER 7 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 6
 ACCESSION NUMBER: 1971:437044 HCAPLUS
 DOCUMENT NUMBER: 75:37044
 TITLE: Polymerization of monoolefins containing carboxylic acid groups with cyclic dienes
 INVENTOR(S): Ihlein, Walter; Galinke, Joachim
 PATENT ASSIGNEE(S): Henkel und Cie. G.m.b.H.
 SOURCE: Ger. Offen., 11 pp.
 CODEN: GWXXBX
 DOCUMENT TYPE: Patent
 LANGUAGE: German
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 1948198	A	19710401	DE 1969-1948198	19690924
DE 1948198	B2	19800703		
DE 1948198	C3	19810312		

PRIORITY APPLN. INFO.: DE 1969-1948198 19690924

IT 32731-90-1P

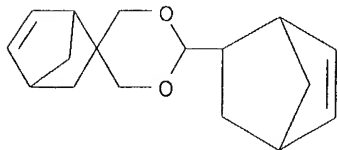
RL: IMF (Industrial manufacture); PREP (Preparation)
 (manufacture of, as thickening agents)

RN 32731-90-1 HCAPLUS

CN Acrylic acid, polymer with endo-2-(5-norbornen-2-yl)spiro[m-dioxane-5,2'-[5]norbornene] (8CI) (CA INDEX NAME)

CM 1

CRN 3781-34-8
 CMF C17 H22 O2



CM 2

CRN 79-10-7
 CMF C3 H4 O2

